

# Table of Contents

## Preface

### Point Defects and Diffusion in Silicon and Gallium Arsenide

U.M. Gösele and T.Y. Tan 1

### Diffusion and Low Temperature Deformation by Diffusional Creep of Nanocrystalline Materials

R. Birringer, H.T. Hahn, H.J. Höfler, J. Karch and H. Gleiter 17

### Dopant and Ion Beam Enhanced Grain Growth in Polycrystalline Silicon Films

C.V. Thompson 33

### Interface Segregation and Cohesion

C.L. White 47

### Oxidation of High Technology Materials

J. Philibert 63

### Interstitial-Substitutional Diffusion in Group III-V and Group IV Semiconductors: The Role of Dislocations

N. Stolwijk, M. Perret and H. Mehrer 79

### Diffusion Barriers - For Thin Film Metallizations

S.P. Murarka 99

### Contact Metallization for GaAs - A Report on the Development of a Non-Alloyed Ohmic Contact Scheme

L.C. Wang, F. Fang, E.D. Marshall and S.S. Lau 111

### High Density Interconnect for Advanced VLSI Packaging

A.C. Adams, R.S. Bentson, W.J. Bertram, H.J. Levinstein, W.Q. McKnight, J.J. Rubin and B.A. ter Haar 129

### Diffusion in Metallic Thin Films

D. Gupta 137

### High Resolution Transmission Electron Microscopy of Grain Boundaries

W. Krakow 151

### Tunneling Microscopy of Surface Diffusion

J.E. Griffith and J.A. Kubby 167

### Characterization of Interfacial Chemistry by Analytical Electron Microscopy

A.D. Romig, Jr. 179

### Solute Interactions in Metals

S.M. Myers 197

### Oxygen Diffusion in High $T_c$ -Superconductors

J.L. Routbort, S.J. Rothman, B.K. Flandermeyer, L.J. Nowicki and J.E. Baker 213

### Tracer Diffusion of $^{60}\text{Co}$ and $^{63}\text{Ni}$ in Amorphous NiZr Alloy

K. Hoshino, R.S. Averback, H.T. Hahn and S.J. Rothman 225

### Tracer Diffusion in Pure and Boron-Doped $\text{Ni}_3\text{Al}$

K. Hoshino, S.J. Rothman and R.S. Averback 233

### The Behavior of Transition Metals in Silicon during Annealing Transients

D.R. Sparks, N.S. Alvi and M.A. Dayananda 239

### Suppression of Vacancy Diffusion during Short Range Ordering

B. Fultz and L. Anthony 253

### Crystallization and Diffusion Studies in Amorphous Ni-Zr Thin Films

G.V. Chandrashekar, D. Gupta, S.B. Newcomb, F.M.H. Spit and K.N. Tu 261

### Compound Formation and Interfacial Instability in the Au-Cu-Sn System at Low Temperature

J.F. Roeder, M.R. Notis and J.I. Goldstein 271